

(FILE 'HOME' ENTERED AT 13:52:07 ON 05 JAN 2005)

FILE 'REGISTRY' ENTERED AT 13:52:16 ON 05 JAN 2005

L1 STRUCTURE UPLOADED
L2 STRUCTURE UPLOADED
L3 STRUCTURE UPLOADED
L4 0 S L1 FULL
L5 10 S L2 FULL
L6 2 S L3 FULL

FILE 'CAPLUS' ENTERED AT 13:54:15 ON 05 JAN 2005

L7 87941 S PHOTSENSITIVE OR PHOTOREACTIVE OR PHOTORESIST
L8 0 S L5 AND L7
L9 0 S L6 AND L7

FILE 'REGISTRY' ENTERED AT 13:55:21 ON 05 JAN 2005

FILE 'CAPLUS' ENTERED AT 13:56:03 ON 05 JAN 2005

L10 8 S L5
L11 3 S L6
L12 1491853 S LIGHT OR RADIATION
L13 0 S (L10 OR L11) AND L12

FILE 'REGISTRY' ENTERED AT 13:58:43 ON 05 JAN 2005

L14 STRUCTURE UPLOADED
L15 STRUCTURE UPLOADED
L16 STRUCTURE UPLOADED
L17 2 S L16 FULL
L18 0 S L14 FULL
L19 0 S L15 FULL

FILE 'CAPLUS' ENTERED AT 14:01:38 ON 05 JAN 2005
S L16

FILE 'REGISTRY' ENTERED AT 14:01:46 ON 05 JAN 2005

L20 0 S L16

FILE 'CAPLUS' ENTERED AT 14:01:47 ON 05 JAN 2005

L21 0 S L20
L22 2 S L17

FILE 'REGISTRY' ENTERED AT 14:18:39 ON 05 JAN 2005

L23 STRUCTURE UPLOADED
L24 STRUCTURE UPLOADED
L25 STRUCTURE UPLOADED
L26 STRUCTURE UPLOADED
L27 STRUCTURE UPLOADED
L28 STRUCTURE UPLOADED
L29 10364 S L23 FULL
L30 326707 S L24 FULL
L31 21 S L25 FULL
L32 0 S L26 FULL
L33 0 S L27 FULL
L34 0 S L28 FULL

FILE 'CAPLUS' ENTERED AT 14:22:32 ON 05 JAN 2005

L35 4111 S L29

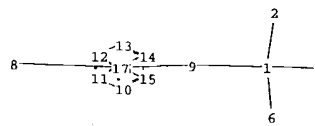
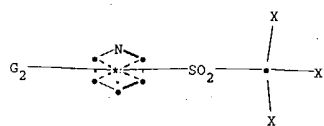
FILE 'REGISTRY' ENTERED AT 14:26:36 ON 05 JAN 2005

L36 858823 S PYRIDINE OR PYRIDINIUM
L37 15228 S L30 AND L36

FILE 'CAPLUS' ENTERED AT 14:27:27 ON 05 JAN 2005

L38 1635 S L37
L39 0 S (L35 OR L38) AND L9
L40 481 S (L35 OR L38) AND L12
L41 169760 S MONOMER
L42 1632352 S POLYMER OR COPOLYMER OR RESIN
L43 187 S L40 AND L42
L44 6 S L43 AND L41

=>

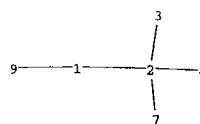
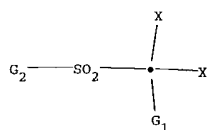


in nodes :
 1 2 3 6 8 9
 g nodes :
 10 11 12 13 14 15
 in bonds :
 1-6 1-2 1-3 1-9
 g bonds :
 10-11 10-15 11-12 12-13 13-14 14-15
 ct bonds :
 1-6 1-2 1-3 1-9
 malized bonds :
 10-11 10-15 11-12 12-13 13-14 14-15

H,CF2,CF3,CCl2,CCl3,CBr2,CBr3,CO2H,COOH,CN,NO2,X

Cb,Cy,Hy,Ak

ch level :
 1:Atom 2:Atom 3:Atom 6:Atom 8:Atom 9:Atom 10:Atom 11:Atom 12:Atom 13:Atom 14:Atom
 15:Atom 16:Atom 17:Atom

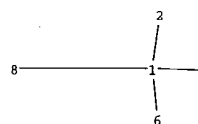
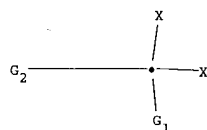


n nodes :
 1 2 3 4 7 9
 n bonds :
 1-2 1-9 2-3 2-4 2-7
 t/norm bonds :
 1-9 2-7
 t bonds :
 1-2 2-3 2-4

,CF2,CF3,CCl2,CCl3,CBr2,CBr3,CO2H,COOH,CN,NO2,X

p,Cy,Hy,Ak

n level :
 1:CLASS 2:CLASS 3:CLASS 4:CLASS 7:CLASS 9:CLASS

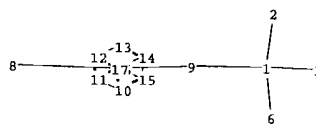
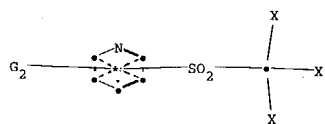


main nodes :
 1 2 3 6 8
 main bonds :
 1-6 1-2 1-3 1-8
 act/norm bonds :
 1-6 1-8
 act bonds :
 1-2 1-3

:H,CF2,CF3,CCl2,CCl3,CBr2,CBr3,CO2H,COOH,CN,NO2,X

:Cb,Cy,Hy,Ak

atch level :
 1:CLASS 2:CLASS 3:CLASS 6:CLASS 8:CLASS



in nodes :
1 2 3 6 8 9

g nodes :
10 11 12 13 14 15

in bonds :
1-6 1-2 1-3 1-9

g bonds :
10-11 10-15 11-12 12-13 13-14 14-15

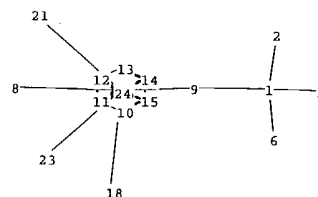
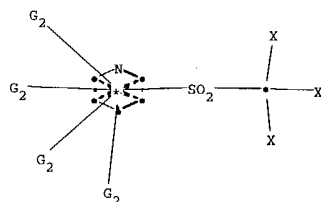
ct bonds :
1-6 1-2 1-3 1-9

malized bonds :
10-11 10-15 11-12 12-13 13-14 14-15

H,CF2,CF3,CCl2,CCl3,CBr2,CBr3,CO2H,COOH,CN,NO2,X

Cb,Cy,Hy,Ak

ch level :
1:CLASS 2:CLASS 3:CLASS 6:CLASS 8:CLASS 9:CLASS 10:Atom 11:Atom 12:Atom 13:Atom
14:Atom 15:Atom 16:CLASS 17:CLASS

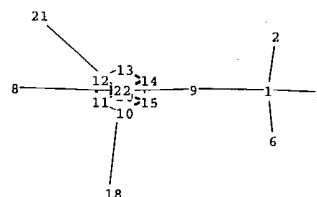
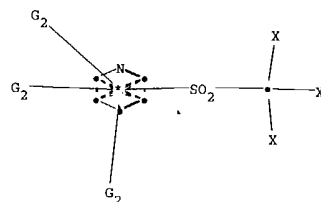


ain nodes :
 1 2 3 6 8 9 18 21 23
 ng nodes :
 10 11 12 13 14 15
 ain bonds :
 1-6 1-2 1-3 1-9
 ng bonds :
 10-11 10-15 11-12 12-13 13-14 14-15
 act bonds :
 1-6 1-2 1-3 1-9
 rmalized bonds :
 10-11 10-15 11-12 12-13 13-14 14-15

:H,CF₂,CF₃,CC12,CC13,CBr₂,CBr₃,CO₂H,COOH,CN,NO₂,X

:Cb,Cy,Hy,Ak

tch level :
 1:Atom 2:Atom 3:Atom 6:Atom 8:Atom 9:Atom 10:Atom 11:Atom 12:Atom 13:Atom 14:Atom
 15:Atom 16:Atom 17:Atom 18:Atom 20:CLASS 21:Atom 22:CLASS 23:Atom 24:CLASS



ain nodes :

1 2 3 6 8 9 18 21

ng nodes :

10 11 12 13 14 15

ain bonds :

1-6 1-2 1-3 1-9

ng bonds :

10-11 10-15 11-12 12-13 13-14 14-15

act bonds :

1-6 1-2 1-3 1-9

ormalized bonds :

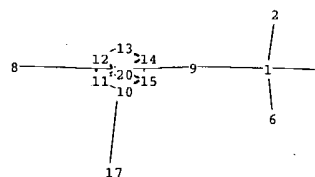
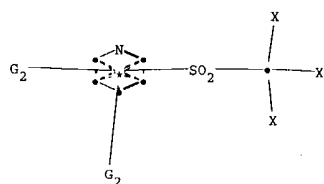
10-11 10-15 11-12 12-13 13-14 14-15

:H,CF2,CF3,CCl2,CCl3,CBr2,CBr3,CO2H,COOH,CN,NO2,X

:Cb,Cy,Hy,Ak

atch level :

1:Atom 2:Atom 3:Atom 6:Atom 8:Atom 9:Atom 10:Atom 11:Atom 12:Atom 13:Atom 14:Atom
15:Atom 16:Atom 17:Atom 18:Atom 20:CLASS 21:Atom 22:CLASS



ain nodes :
 1 2 3 6 8 9 17
 ng nodes :
 10 11 12 13 14 15
 ain bonds :
 1-6 1-2 1-3 1-9
 ng bonds :
 10-11 10-15 11-12 12-13 13-14 14-15
 act bonds :
 1-6 1-2 1-3 1-9
 rmalized bonds :
 10-11 10-15 11-12 12-13 13-14 14-15

H,CF₂,CF₃,CCl₂,CCl₃,CBr₂,CBr₃,CO₂H,COOH,CN,NO₂,X

Cb,Cy,Hy,Ak

ech level :
 1:Atom 2:Atom 3:Atom 6:Atom 8:Atom 9:Atom 10:Atom 11:Atom 12:Atom 13:Atom 14:Atom
 15:Atom 16:Atom 17:Atom 19:CLASS 20:CLASS

claims

L44 ANSWER 6 OF 6 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1996:537256 CAPLUS

DN 125:181358

TI Photosensitive **resin** composition, photosensitive printing plate
and method of manufacturing printing master plate

IN Iwai, Takeshi; Komano, Hiroshi

PA Tokyo Ohka Kogyo Co., Ltd., Japan

SO Eur. Pat. Appl., 24 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 720053	A2	19960703	EP 1995-120733	19951229
	EP 720053	A3	19960821		
	EP 720053	B1	20020904		
	R: DE, FR, GB, IT				
	JP 08240908	A2	19960917	JP 1995-351263	19951227
	US 5885746	A	19990323	US 1995-580356	19951228
PRAI	JP 1994-339107	A	19941229		

OS MARPAT 125:181358

TI Photosensitive **resin** composition, photosensitive printing plate
and method of manufacturing printing master plate

AB A photosensitive **resin** composition comprises a high **polymer**
binder, a **monomer**, a photopolymer. initiator generating a radical
on exposure to visible **light** of a wavelength of 400 to 700 nm
such as triazine compds., titanocene compds., or acridine compds., an
optically activated acid-generating agent generating an acid on exposure
to **light** of a wavelength of 200 to 380 nm, and a color former
developing a color in the presence of an acid and a method manufacturing a
printing master plate comprises the steps of exposing a photosensitive
printing plate which has a laminated layer made from a photosensitive
resin composition thereon to visible **light** of wavelength in
the range of 400 to 600 nm selectively in an imagewise configuration in
order to harden the **resin** composition layer, developing the
photosensitive printing plate, and further exposing the developed plate to
light of a wavelength in the range 200 to 38 nm. The
photosensitive **resin** composition has a wide range of wavelengths of
light to which the **resin** composition is sensitive on exposure
and forms a good image with visible laser and the photosensitive printing
plate is excellent in pattern distinctiveness, easy in handling, and
excellent in working efficiency. The method is useful in an industrial
field due to simplicity and easiness in view of the fact that it includes
only the main steps of exposing the photosensitive printing plate to
visible **light** of a wavelength of 400 to 700 nm and then to
light of a wavelength of 200 to 380 nm which is shorter than the
former.

IT Lithographic plates

Printing plates

(photopolymerizable compns. containing visible **light**-sensitive
photopolymer. initiators, photosensitive acid generators, and color
developers for manufacture of)

IT 95-71-6, Methylhydroquinone 594-65-0, Trichloroacetamide 602-56-2
1552-42-7 5339-80-0 15625-89-5, Trimethylolpropane triacrylate
34372-72-0 38371-56-1 92780-17-1 125051-32-3 171063-85-7,
Acrylic acid-benzyl methacrylate-2-hydroxyethyl methacrylate-methyl
methacrylate copolymer 172600-77-0 180511-68-6

RL: TEM (Technical or engineered material use); USES (Uses)

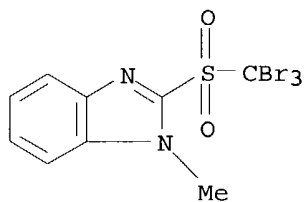
(printing plate preparation using photopolymerizable compns. containing)

IT 38371-56-1 180511-68-6

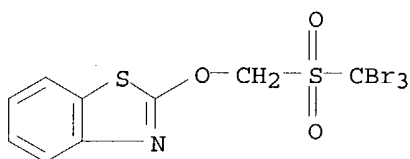
RL: TEM (Technical or engineered material use); USES (Uses)

(printing plate preparation using photopolymerizable compns. containing)

RN 38371-56-1 CAPLUS
CN 1H-Benzimidazole, 1-methyl-2-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



RN 180511-68-6 CAPLUS
CN Benzothiazole, 2-[[[(tribromomethyl)sulfonyl]methoxy]- (9CI) (CA INDEX NAME)



=>

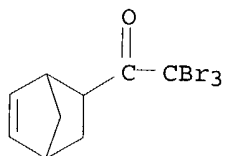
Sulfone
= sulfonyl.

10/687,689

ResHs

L35 ANSWER 6 OF 10 CAPLUS COPYRIGHT 2004 ACS on STN
 AN 2002:353506 CAPLUS
 DN 136:377479
 TI High-molecular compounds for photoresists, monomeric compounds,
photosensitive resin compositions, method for forming patterns
 with the compositions, and process for production of electronic components
 IN Shida, Naomi; Ushirogouchi, Toru; Naito, Takuya
 PA Kabushiki Kaisha Toshiba, Japan
 SO PCT Int. Appl., 321 pp.
 CODEN: PIXXD2
 DT Patent
 LA Japanese
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2002036646	A1	20020510	WO 2001-JP9567	20011031
	W: KR, US				
	JP 2002201219	A2	20020719	JP 2001-295012	20010926
	US 2003235781	A1	20031225	US 2003-425848	20030430
PRAI	JP 2000-332358	A	20001031		
	JP 2001-295012	A	20010926		
	WO 2001-JP9567	A1	20011031		
OS	MARPAT 136:377479				
AB	High-mol. compds. for photoresists, each having at least one skeleton represented by the general formula -RC(Rx1)2(ORx1), I, II, or III: -RC(Rx1)2(ORx1) I II III (R = alicyclic skeleton; Rx1= electron-attracting group, H, monovalent organic group). The compds. shows small absorption towards ≤ 160 nm light and provides the fine resist pattern of nanometer size and of the high etching resistance.				
IT	424826-69-7				
	RL: RCT (Reactant); RACT (Reactant or reagent) (monomer of high-mol. compds. for photoresists)				
RN	424826-69-7 CAPLUS				
CN	Ethanone, 1-bicyclo[2.2.1]hept-5-en-2-yl-2,2,2-tribromo- (9CI) (CA INDEX NAME)				



RE.CNT 23 THERE ARE 23 CITED REFERENCES AVAILABLE FOR THIS RECORD
 ALL CITATIONS AVAILABLE IN THE RE FORMAT

L35 ANSWER 7 OF 10 CAPLUS COPYRIGHT 2004 ACS on STN
 AN 1998:361179 CAPLUS
 DN 129:101950
 TI **Photosensitive** colored composition containing three-component
 polymerization initiator system for color filter and the color filter
 IN Higuchi, Yoichi
 PA Dai Nippon Printing Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF

DT Patent
 LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 10153860	A2	19980609	JP 1996-325904	19961122

PRAI JP 1996-325904

19961122

OS MARPAT 129:101950

AB The title composition comprises a **photosensitive** resin component containing a colorant, an organic polymer, and a photopolymer. **monomer**, a solvent, and a 3-component photopolymer. initiator system comprising (a) (4-hydroxy-1-naphthalenyl)dimethylsulfonium salt with SbF₆⁻ or CFSO₃⁻, (b) tribromomethyl Ph sulfone or p-C₆H₄C(O)CH₂Brn (R = H, NO₂; m = 0, 1; n = 2, 3), and (b) an amine. A color filter fabricated from the composition is also claimed. The photopolymer. initiator system with enhanced radical life and efficient photopolymer. provides the color filter with improved adhesion to substrate.

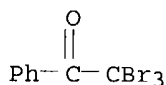
IT 7402-45-1, 2,2,2-Tribromoacetophenone 13665-04-8,
2,2-Dibromoacetophenone

RL: CAT (Catalyst use); USES (Uses)

(initiator; **photosensitive** polymer composition containing
three-component photopolymer. initiator system with enhanced radical
life for color filter)

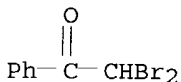
RN 7402-45-1 CAPLUS

CN Ethanone, 2,2,2-tribromo-1-phenyl- (9CI) (CA INDEX NAME)



RN 13665-04-8 CAPLUS

CN Ethanone, 2,2-dibromo-1-phenyl- (9CI) (CA INDEX NAME)



L35 ANSWER 8 OF 10 CAPLUS COPYRIGHT 2004 ACS on STN

AN 1981:559910 CAPLUS

DN 95:159910

TI Plasma developable **photoresist** composition with polyvinyl formal
binder

IN Lewis, James M.; McInerney, Eugene F.

PA Horizons Research, Inc., USA

SO U.S., 5 pp.

CODEN: USXXAM

DT Patent

LA English

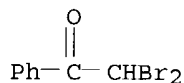
FAN.CNT 1

Binder
N-vinyl monomer N-vinyl carbazole
P.I. org. halogen

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 4278753	A	19810714	US 1980-124413	19800225
	JP 57196229	A2	19821202	JP 1981-79940	19810526
	JP 01049928	B4	19891026		
PRAI	US 1980-124413		19800225		

AB **Photoresist** compns. which may be completely processed by dry techniques, especially by use of an O₂ plasma, are composed of an N-vinyl **monomer** and an organic H compound in a binder which contributes significantly to the utility of the composition in the fabrication of microelectronic devices. Thus, a composition containing N-vinylcarbazole 3.34, 2,6-di-tert-butyl-p-cresol 0.33, CH₃I 2.81, Butvar B-724 6.12, and a PrOH-BuOH (1:1) mixture 100 g was spin coated on an oxidized Si wafer, dried to give a layer of 10,000 Å thickness, imagewise exposed using a high resolution test pattern, and developed using an O₂ plasma for 6 min to give complete resolution of the original pattern.

IT 13665-04-8
RL: TEM (Technical or engineered material use); USES (Uses)
(photoresist compns. containing, oxygen plasma-developable)
RN 13665-04-8 CAPLUS
CN Ethanone, 2,2-dibromo-1-phenyl- (9CI) (CA INDEX NAME)



L35 ANSWER 9 OF 10 CAPLUS COPYRIGHT 2004 ACS on STN
AN 1974:497798 CAPLUS
DN 81:97798
TI Light sensitive reproduction and electron beam-sensitive material
IN Lewis, James M.; Wainer, Eugene
PA Horizons Research Inc.
SO U.S., 18 pp. Division of U.S. 3,769,023.
CODEN: USXXAM

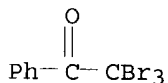
DT Patent
LA English

FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 3820993	A	19740628	US 1973-371431	19730619
	US 3769023	A	19731030	US 1971-141393	19710507
PRAI	US 1971-141393	A3	19710507		

AB Light-sensitive and electron-beam sensitive photopolymerizable compns. composed of an ethylenically unsatd. N-vinyl monomer, ≥ 1 organic compound capable of forming free radicals on exposure to a suitable dose of radiation, and a hydroxypropyl cellulose with a mol. weight of .apprx.25,000-1,000,000 as the binder are useful in preparing pos. and/or neg. copies, planog. and deep etch lithog. plates, thin and thick film printed circuits. Thus, a solution containing N-vinylcarbazole 150, 2,6-di-tert-butyl-p-cresol 50, Ph3Sb 10, 3-ethylrhodanine 50, CHI3 100, hydroxypropyl cellulose (mol. weight 50,000) 400 g, CH2Cl2 4000 cm3, and THF 2000 cm3 was coated on a subbed poly(ethylene terephthalate) support to a 3 mil wt thickness, dried at 90° for 30 sec, exposed through a step wedge for a total exposure of 150 mJ using 7 15-W black light fluorescent lamps, and the faint greenish yellow image fixed at 170° for 90 sec to give a Dmax. of 2.22.

IT 7402-45-1
RL: USES (Uses)
(photoinitiator, for photopolymerizable compns. for electron-beam resist, photoresist, and photog. applications)
RN 7402-45-1 CAPLUS
CN Ethanone, 2,2,2-tribromo-1-phenyl- (9CI) (CA INDEX NAME)



L35 ANSWER 10 OF 10 CAPLUS COPYRIGHT 2004 ACS on STN
AN 1974:444148 CAPLUS
DN 81:44148
TI Light sensitive reproduction and electron beam-sensitive material
IN Lewis, James Marvin; Wainer, Eugene
PA Horizons Inc.
SO U.S., 17 pp.

CODEN: USXXAM

DT Patent
LA English
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 3769023	A	19731030	US 1971-141393	19710507
	US 3820993	A	19740628	US 1973-371431	19730619
PRAI	US 1971-141393	A3	19710507		

AB A light- and electron beam-sensitive composition useful for preparing pos. or neg.

copies, planog. and deep-etched printing plates and printed circuits consists of (1) a hydroxyalkylcellulose, (2) an ethylenically unsatd. vinyl monomer, (3) a compound which produces free radicals on exposure to light or electron beams, (4) a color former which produces color by reacting with oxidizing agents or acids, (5) an organic S compound, and (6) agents for improving the shelf stability. Thus, a solution prepared from N-vinylcarbazole 150, 2,6-di-tert-butyl-p-cresol 50, triphenylstibine 10, 3-ethylrhodanine 50, CHI₃ 100, hydroxy-propylcellulose 400 g, CH₂Cl₂ 4000, and THF 2000 ml was coated on a subbed polyethylene terephthalate support as a 3 mil layer, dried at 90°, exposed to UV radiation (with a total exposure of 150 mJ) through a stepwedge, and developed by heating at 170° for 90 sec to give a yellow-green image with a Dmax. of 2.22.

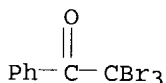
IT 7402-45-1

RL: USES (Uses)

(photoresist compns. containing vinyl compds., hydroxyalkyl cellulose and, for printed elec. circuits and printing plates)

RN 7402-45-1 CAPLUS

CN Ethanone, 2,2,2-tribromo-1-phenyl- (9CI) (CA INDEX NAME)



=>

NO

- (1) cellulose = Binder col 4!
- (2) Monomer = col. 5 / CL col 6
(N-vinyl monomer)
- (3) In = color former col. 7
- (4) color former col. 7 + 8
- (5) org. S. compd. promot. adhesion
- (6) STAB. agent.

2003:240174 CAPLUS

DN 138:262621
TI Heat-developable photographic material containing polymer with polyhalo group and image formation
IN Fukusaka, Kiyoshi; Miura, Norio
PA Konica Co., Japan
SO Jpn. Kokai Tokkyo Koho, 29 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003091054	A2	20030328	JP 2001-391507	20011225
PRAI	JP 2001-209181	A	20010710		

AB The material contains a polymer having ≥ 1 aliphatic **monomer** releasing halogen radical as a repeating unit. The material contains a polymer having ≥ 1 repeating unit $ZAm(YCRX1X2)q$ ($X1-2 = \text{halo}, R = H, \text{halo}, \text{substituent}, ; Y = \text{OCO}, \text{NR1CO}; R1 = H, \text{halo}, \text{substituent}; q = 1-3; A = \text{aromatic or heterocycle}; m = 0, 1; Z = \text{ethylenic unsatd. group, ethyleneimino, epoxy}$). The material has ≥ 1 photog. constitutive layer containing ≥ 1 polymer with ≥ 1 repeating unit $CH(OLCR2X3X4)rCH2$ ($X3-4 = \text{halo}; R2 = H, \text{halo}, \text{substituent}; L = \text{divalent linkage}; r \geq 1$) in polyvinyl butyral unit. The material has a layer containing an organic Ag salt, a **photosensitive** Ag halide, and a binder on a support. The material is exposed with laser beam and developed at $80-250^\circ$. The material shows high sensitivity, good storage stability, and gives clear Ag tone images without fog.

IT 503047-32-3 503047-33-4 503047-35-6

503047-37-8 503047-39-0 503047-41-4

RL: TEM (Technical or engineered material use); USES (Uses)

(heat-developable photog. film containing polymer with halogen radical-releasing unit)

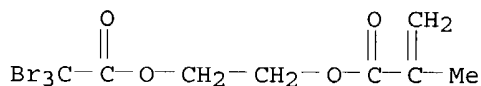
RN 503047-32-3 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[(tribromoacetyl)oxy]ethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 66992-19-6

CMF C8 H9 Br3 O4



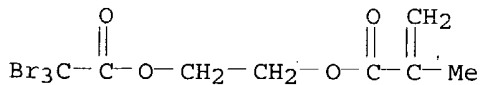
RN 503047-33-4 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[(tribromoacetyl)oxy]ethyl ester, polymer with butyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

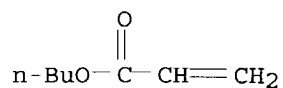
CRN 66992-19-6

CMF C8 H9 Br3 O4



CM 2

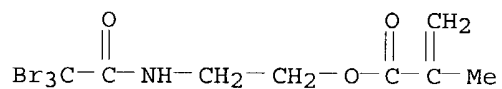
CRN 141-32-2
CMF C7 H12 O2

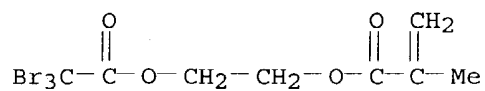


RN 503047-35-6 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[(tribromoacetyl)amino]ethyl ester,
homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 503047-34-5
CMF C8 H10 Br3 N O3

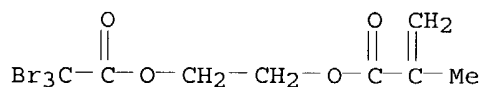




RN 503047-33-4 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[(tribromoacetyl)oxy]ethyl ester, polymer
 with butyl 2-propenoate (9CI) (CA INDEX NAME)

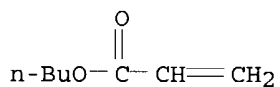
CM 1

CRN 66992-19-6
 CMF C8 H9 Br3 O4



CM 2

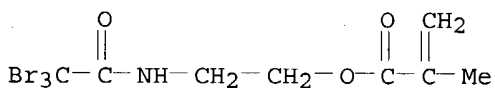
CRN 141-32-2
 CMF C7 H12 O2

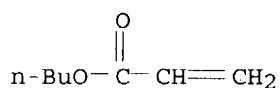


RN 503047-35-6 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[(tribromoacetyl)amino]ethyl ester,
 homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 503047-34-5
 CMF C8 H10 Br3 N O3





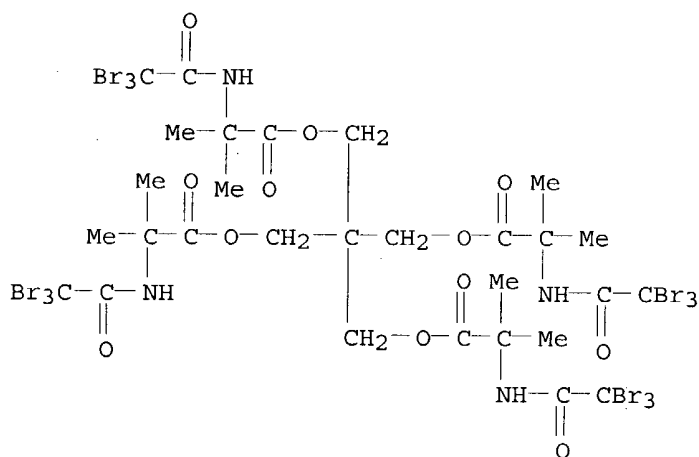
IT 496871-55-7 503047-42-5

RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)

(heat-developable photog. film containing polymer with halogen radical-releasing unit and polyhalo compound)

RN 496871-55-7 CAPLUS

CN Alanine, 2-methyl-N-(tribromoacetyl)-, tetraester with 2,2-bis(hydroxymethyl)-1,3-propanediol (9CI) (CA INDEX NAME)



RN 503047-42-5 CAPLUS

CN Acetamide, N,N',N''-[7-(acetyloxy)tricyclo[3.3.1.1^{3,7}]decane-1,3,5-triyl]tris[2,2,2-tribromo- (9CI) (CA INDEX NAME)

